



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/669,667
 Filing Date September 23, 2003
 Confirmation No. 5558
 Inventor Li Li et al.
 Assignee Micron Technology, Inc.
 Group Art Unit 1722
 Examiner Felisa Carla Hiteshew
 Attorney's Docket No. MI22-2144
 Customer No. 021567
 Title: Atomic Layer Deposition Methods of Forming Silicon Dioxide
 Comprising Layers

RESPONSE TO JUNE 2, 2005 OFFICE ACTION

To: Mail Stop Amendment
 Commissioner for Patents
 P. O. Box 1450
 Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
 Wells St. John P.S.
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Responsive to the Office Action dated June 2, 2005, Applicant amends
 and remarks as follows:

AMENDMENTS